

BENEQ P800

The Beneq P800 is a production-proven batch ALD system perfect for industrial manufacturing. Boasting a vacuum chamber with a diameter of 800 mm, this tool provides ample space for high volume coating production while still providing excellent batch uniformity. It is ideal for depositing thick optical coatings and etch-resistant barrier films.



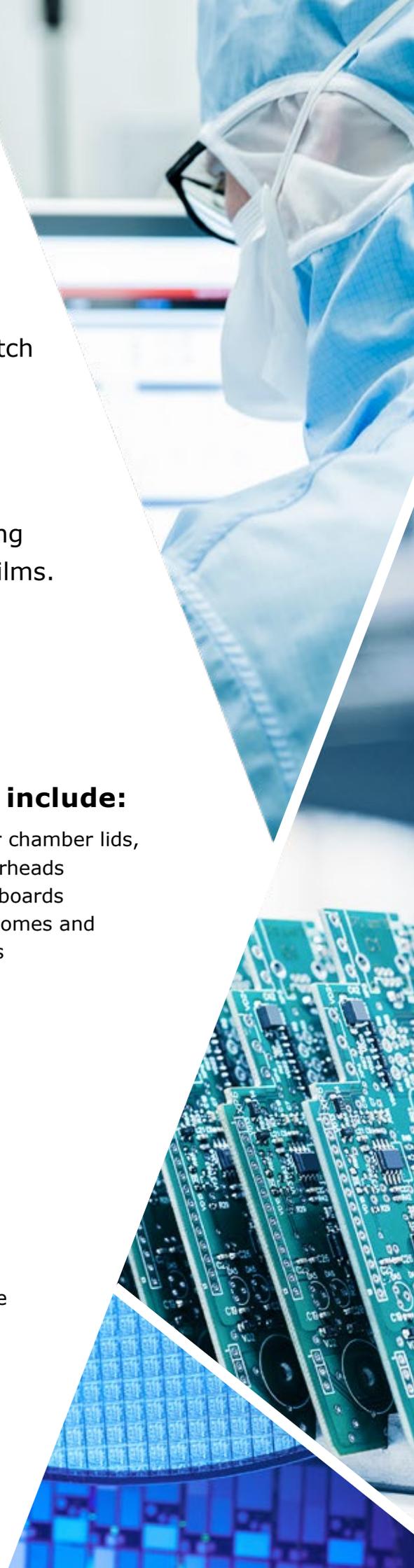
Example substrates include:

- Semiconductor chamber lids, liners & showerheads
- Printed circuit boards
- Large optical domes and freeform optics

SIZE: Coat parts with diameters larger than 600 mm or use the P800's capacity to easily scale up your batch size of smaller parts without compromising film quality and uniformity.

FLEXIBILITY: The P800 offers customizable reaction chamber sizes optimized for your substrate and application. Reaction chambers are easily switchable for easy maintenance and maximum tool uptime.

ROBUSTNESS: Beneq P800 is equipped with high-capacity precursor sources, deactivation and filtration systems to enable easy deposition of micron-thick film stacks.



BENEQ P800 Specifications

PROCESS TYPE	Thermal ALD
INTEGRATION	Stand-alone
DIMENSIONS	3200 × 1340 × 2460 mm
VACUUM CHAMBER DIMENSIONS	Ø: 800 mm
TEMPERATURE RANGE	25–550 °C
SUBSTRATE TYPE	Wafers Glass or metal sheets 3D and freeform parts
SUBSTRATE SPACE EXAMPLE	550 × 310 × 700 mm 730 × 1200 × 10 mm

Beneq Batch Production Equipment

Beneq's P-Series provides the largest scale, general purpose ALD production systems ideal for coating diverse substrate types and thick films. Easily scale up ALD deposition from the R&D phase to full manufacturing workflows.



Beneq P400A

Optimized at the intersection of deposition rate, batch size and uniformity.



Beneq P800

Perfect system for industrial batch production and manufacturing.



Beneq P1500

World's biggest ALD system for coating large substrates and batches.

